## Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

 (Currently Amended) A norbornane lactone (meth)acrylate represented by the following general formula (1):

$$CH_{2} = C$$

$$O(R_{1}O)n$$

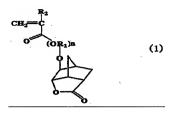
$$CH_{2} = C$$

$$O(R_{1})n$$

$$O$$

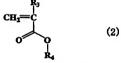
where (wherein  $R_1$  denotes an alkylene group having 2 to 4 carbon atoms, n denotes an integer of 1 to 3, and  $R_2$  denotes a hydrogen atom or methyl-group.) group.

2. (Currently Amended) A- $\frac{1}{(eo)polymer copolymer}$  obtained by polymerizing a monomer mixture containing norbornane lactone (meth)acrylate represented by the following general formula (1):



where R<sub>1</sub> denotes an alkylene group having 2 to 4 carbon atoms, n denotes an integer of 1 to 3, and R<sub>2</sub> denotes a hydrogen atom or methyl group.

3. (Currently Amended) The copolymer according to claim 2 which is obtained by polymerizing a monomer mixture containing at least one-of-compounds compound represented by-the general formula (1) and at least one of compounds expressed by the following general formula (2):



where (wherein R<sub>3</sub> denotes a hydrogen atom or methyl group, R<sub>4</sub> denotes a substituted or unsubstituted hydrocarbon group having 3 to 19 carbon-atoms) atoms, and whose weight-average molecular weight (Mw) is 2000 to 200000.

- (Currently Amended) <u>A photoresist material comprising the copolymer</u>
   according to claim 2. The (eo)polymer according to claim 2, which is used as photoresist material.
- 5. (Currently Amended) A photoresist material comprising the copolymer according to claim 3. The (eo)polymer according to claim 3, which is used as photoresist material.